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(12) **United States Design Patent** (10) **Patent No.:** **US D868,995 S**  
**Tanaka et al.** (45) **Date of Patent:** **\*\* Dec. 3, 2019**

(54) **GAS DIFFUSION PLATE FOR A PLASMA PROCESSING APPARATUS**

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(\*\*) Term: **15 Years**

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(30) **Foreign Application Priority Data**

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(51) **LOC (12) Cl.** ..... **24-02**

(52) **U.S. Cl.**  
USPC ..... **D24/225**

(58) **Field of Classification Search**  
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D24/193, 197, 216, 225; D23/200,  
D23/213-215, 222, 223, 229, 283, 269;  
D15/140, 17, 126, 138, 176; D13/182;  
D12/212; D8/66, 358, 375  
CPC ..... H01J 37/32082; H01J 37/32541; H01L  
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See application file for complete search history.

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(57) **CLAIM**

The ornamental design for a gas diffusion plate for a plasma processing apparatus, as shown and described.

**DESCRIPTION**

FIG. 1 is a front, bottom and right side perspective view of a gas diffusion plate for a plasma processing apparatus according to the design;

FIG. 2 is a front elevational view thereof;

FIG. 3 is a left side elevational view thereof;

FIG. 4 is a right side elevational view thereof;

FIG. 5 is a top plan view thereof;

FIG. 6 is a bottom plan view thereof;

FIG. 7 is a rear elevational view thereof;

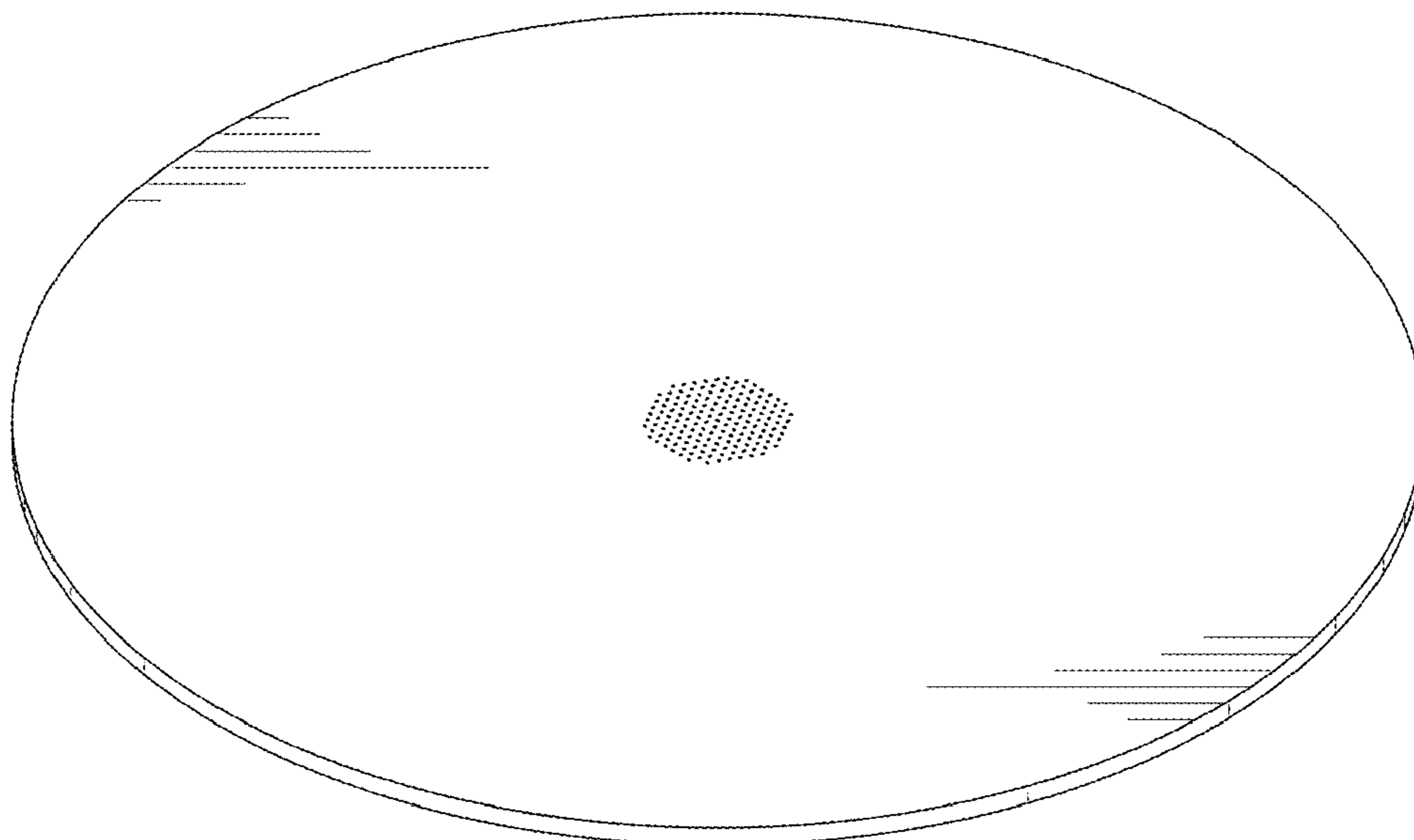
FIG. 8 is a cross-sectional view taken along line 8-8 of FIG. 2;

FIG. 9 is an enlarged view of the portion shown in BOX 9 in FIG. 2; and,

FIG. 10 is an enlarged view of the portion shown in BOX 10 in FIG. 8.

The broken lines show the boundary of enlarged portions and form no part of the claimed design.

**1 Claim, 4 Drawing Sheets**



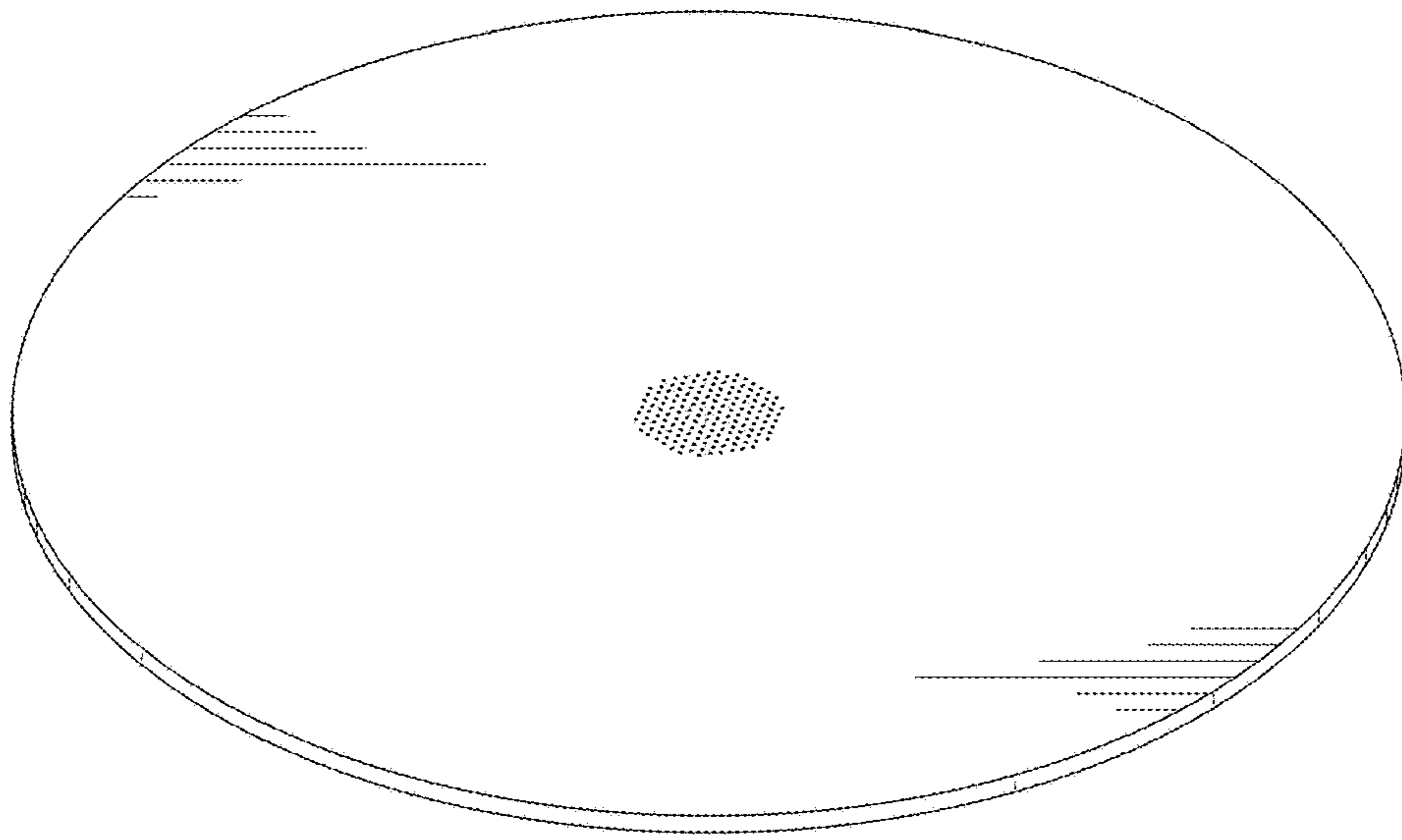


FIG. 1

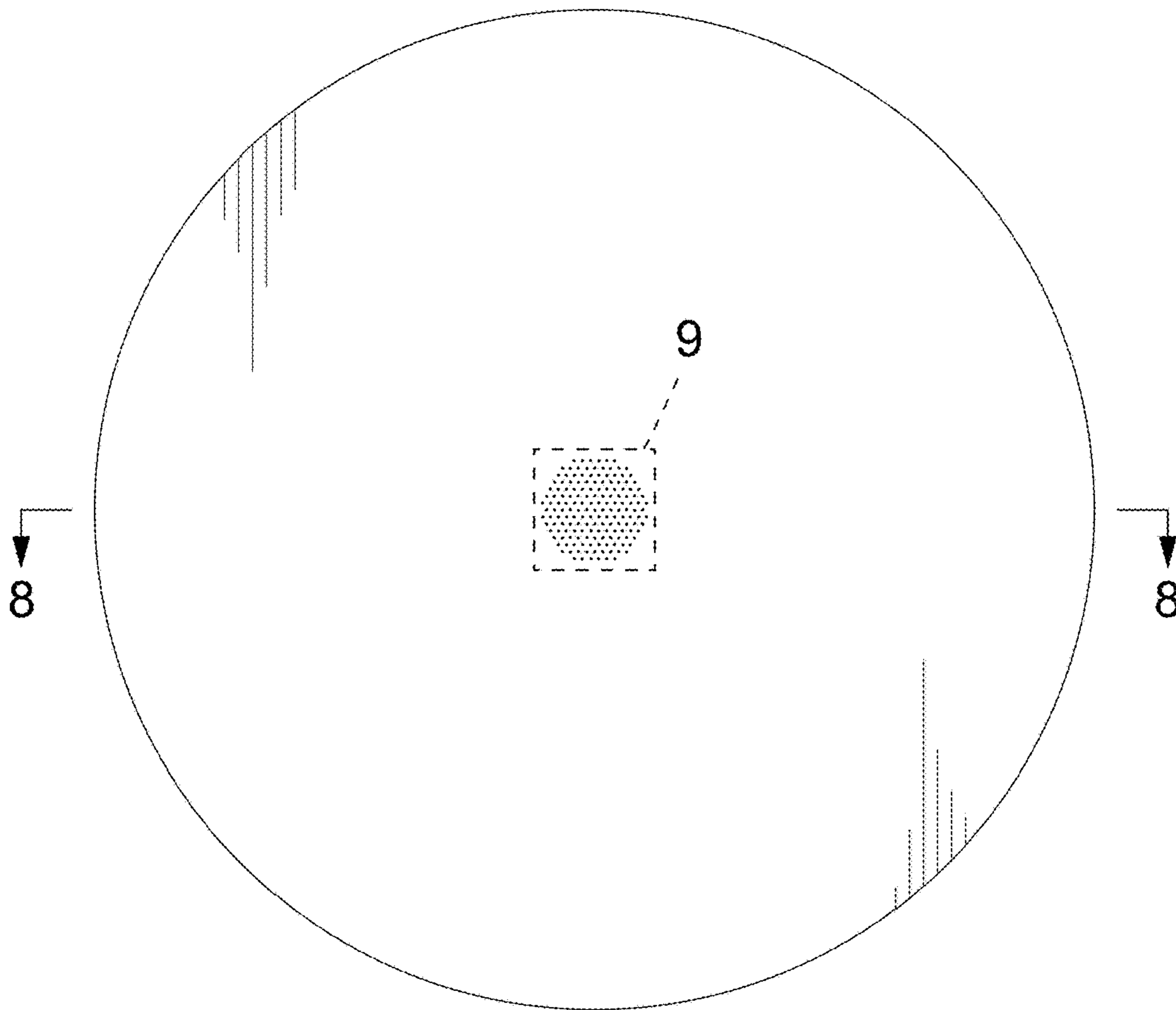
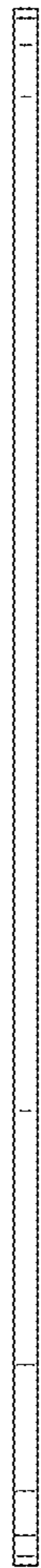
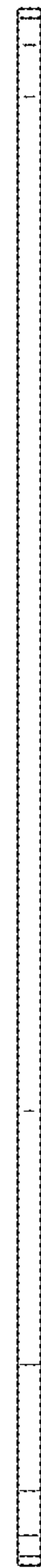


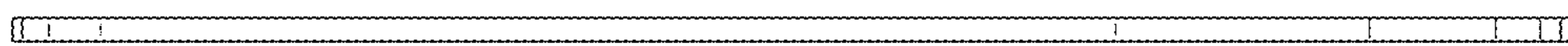
FIG. 2



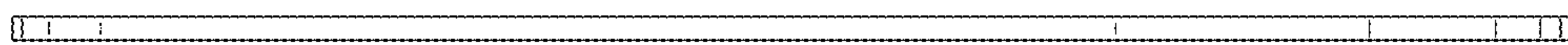
*FIG. 3*



*FIG. 4*



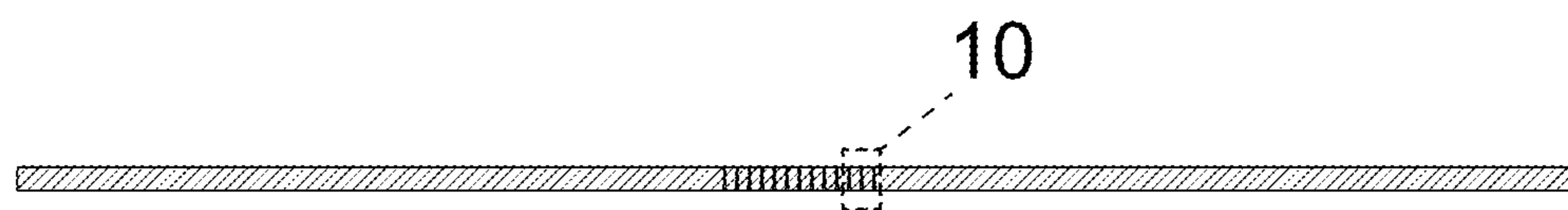
*FIG. 5*



*FIG. 6*



**FIG. 7**



**FIG. 8**

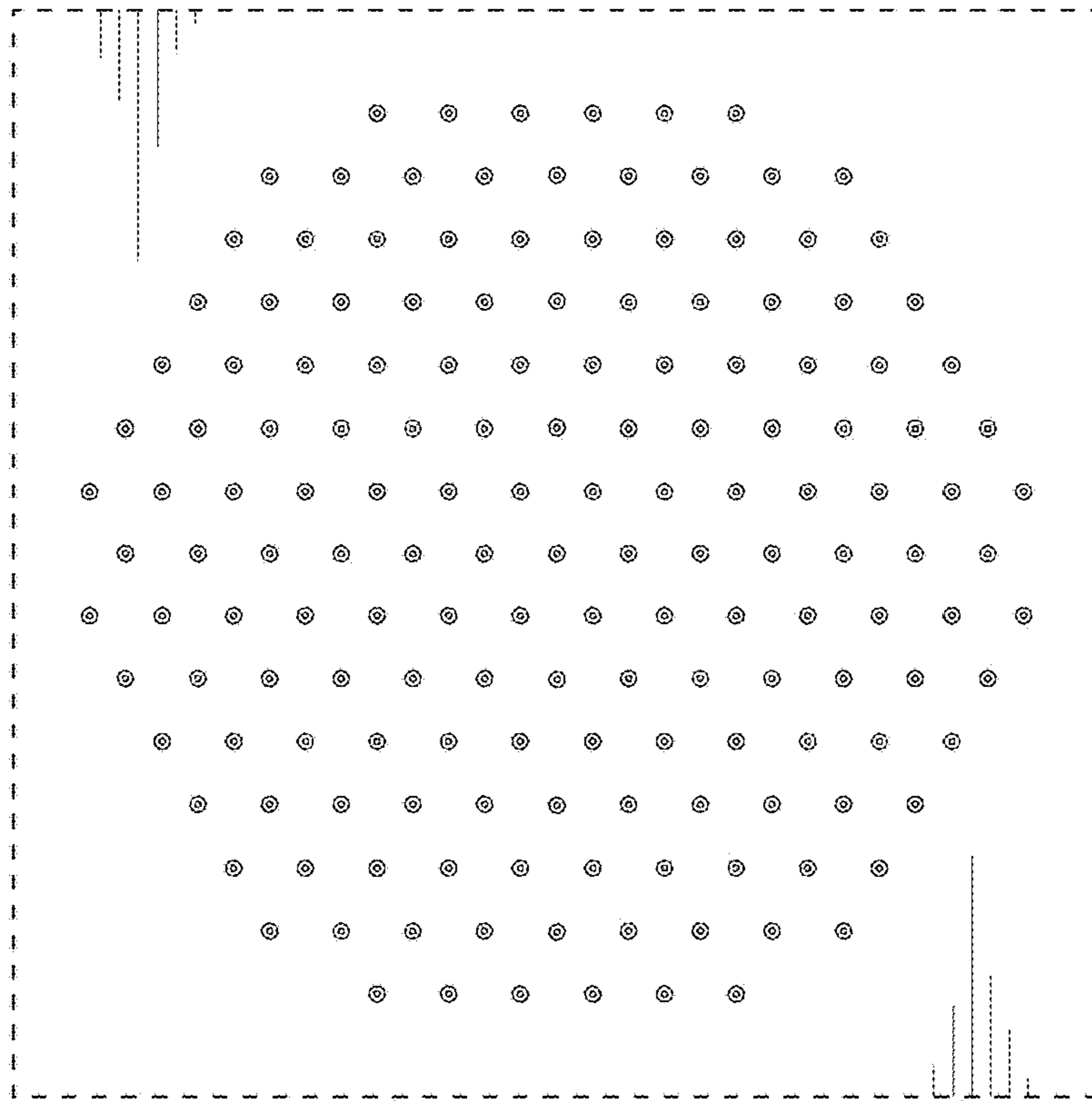


FIG. 9

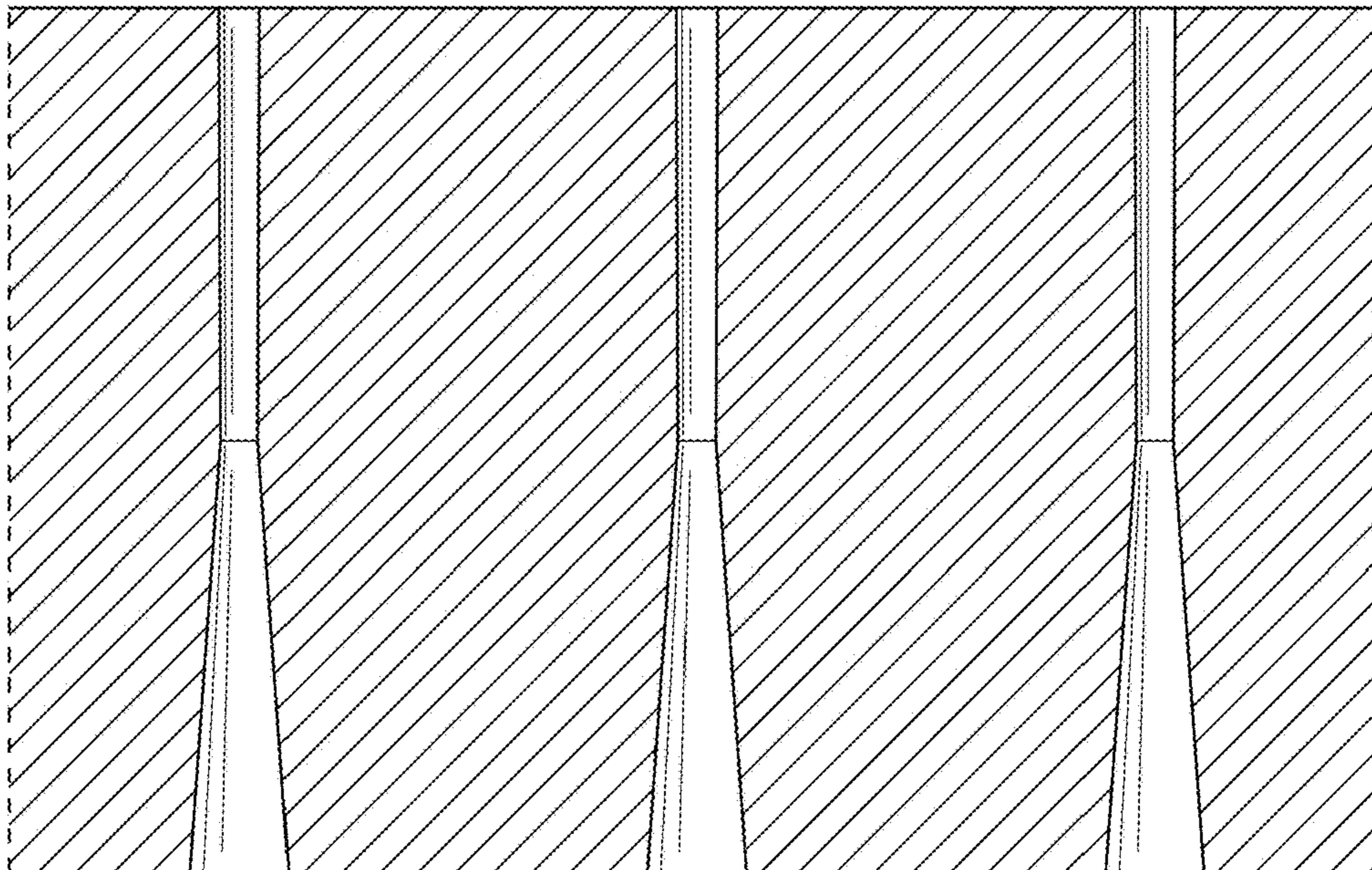


FIG. 10